

AMENDMENTS TO THE SPECIFICATION:

Please amend the specification as follows:

On page 1, line 1, by inserting the following new paragraph:

This is a division of Application No. 09/783,295, filed February 15, 2001, and claims the benefit of Japanese Patent Application No. 2000-036690, filed February 15, 2000, which are incorporated herein by reference.

On page 12, replace the paragraphs beginning on line 7 through line 13 with the following paragraphs:

FIGS. ~~6A to 6H~~ 6A, 6B, 6C, 6D, 6E, 6F, 6G, and 6H are views showing a modification example of the embodiment in which inspections are made in a method of changing the duty ratio;

FIGS. ~~7A to 7H~~ 7A, 7B, 7C, 7D, 7E, 7F, 7G, and 7H are views showing a modification example of the embodiment in which diffraction patterns having a plurality of periods are used to make an inspection;

On page 12, replace the paragraph beginning on line 19 through line 21 with the following paragraph:

FIGS. ~~9A to 9C~~ 9A, 9B, and 9C are views showing the entire structure of a photomask used in the second embodiment of the present invention;

On page 13, replace the paragraph beginning on line 20 through line 22 with the following paragraph:

FIGS. ~~18A and 18C~~ 18A, 18B, and 18C are plan views showing modification examples of photomasks of the present invention;